

U.S. Department of Commerce, Patent and Trademark INFORMATION DISCLOSURE STATEMENT BY APPLICANT SEP 04 2003 RECEIVED SEP 08 2003 TC 1700	Atty. Docket No.	Application No.
	TNCR.196US0	09/833,084
	Applicant(s)	
	Abdulhalim et al.	
(Use several sheets if necessary)	Filing Date	Group
	4/10/01	1775

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	2	5,607,818	3/4/97	Akram et al.			
	3	5,738,961	4/14/98	Chen et al.			
30	4	5,877,861	3/2/99	Ausschnitt et al.			

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		Document	Date	Country	Class	Subclass	Yes	No

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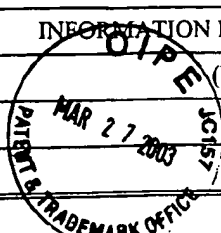
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9/4/03

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	Ibrahim Abdulhalim, et al.	8866
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Examiner <i>Galau</i>	Date Considered <i>6/7/04</i>
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A7				
A8				

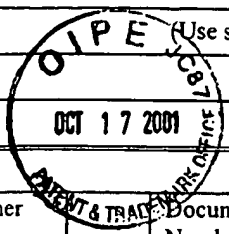
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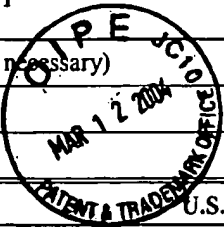
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(Use several sheets if necessary)				Abdulhalim, Ibrahim; Abel, Mike; Faeyman,				
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	AF							
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	AH							
	AI							
	AJ							
	AK							
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							Translation	
	Document	Date	Country	Class	Subclass	Yes	No	
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(Use several sheets if necessary)		Ibrahim Abdulhalim, et al.		8866	
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		Document	Date	Country	Class	Subclass	Yes	No

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Examiner <i>JS</i>	Date Considered <i>6/7/04</i>
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3/12/04

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	Ibrahim Abdulhalim, et al.	8866
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